

Making integrated circuits

2012-03-14

Carsten Wulff

Outline

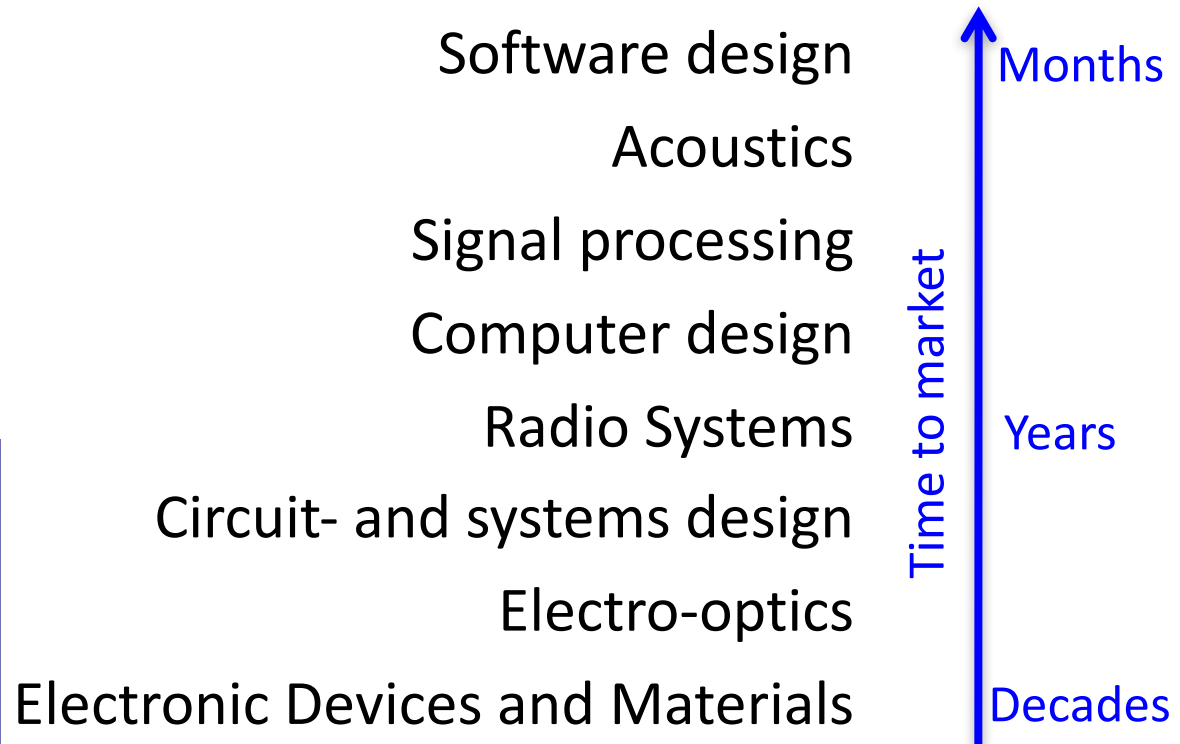
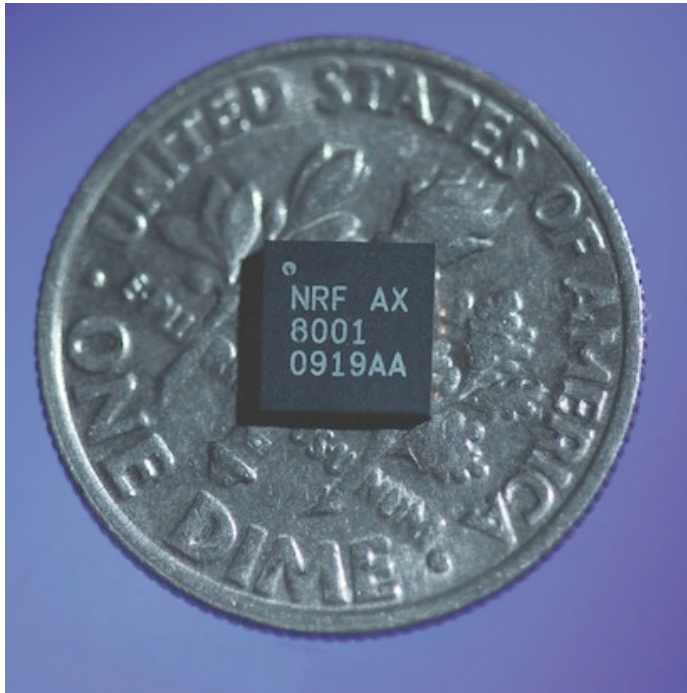
- Compulsory introduction: who am I, what have I done, and what do I do, where do I work, what to they do....
- Circuit elements
- Processing
- Layout
- Schematics
- Advice for electronics students

Who am I?

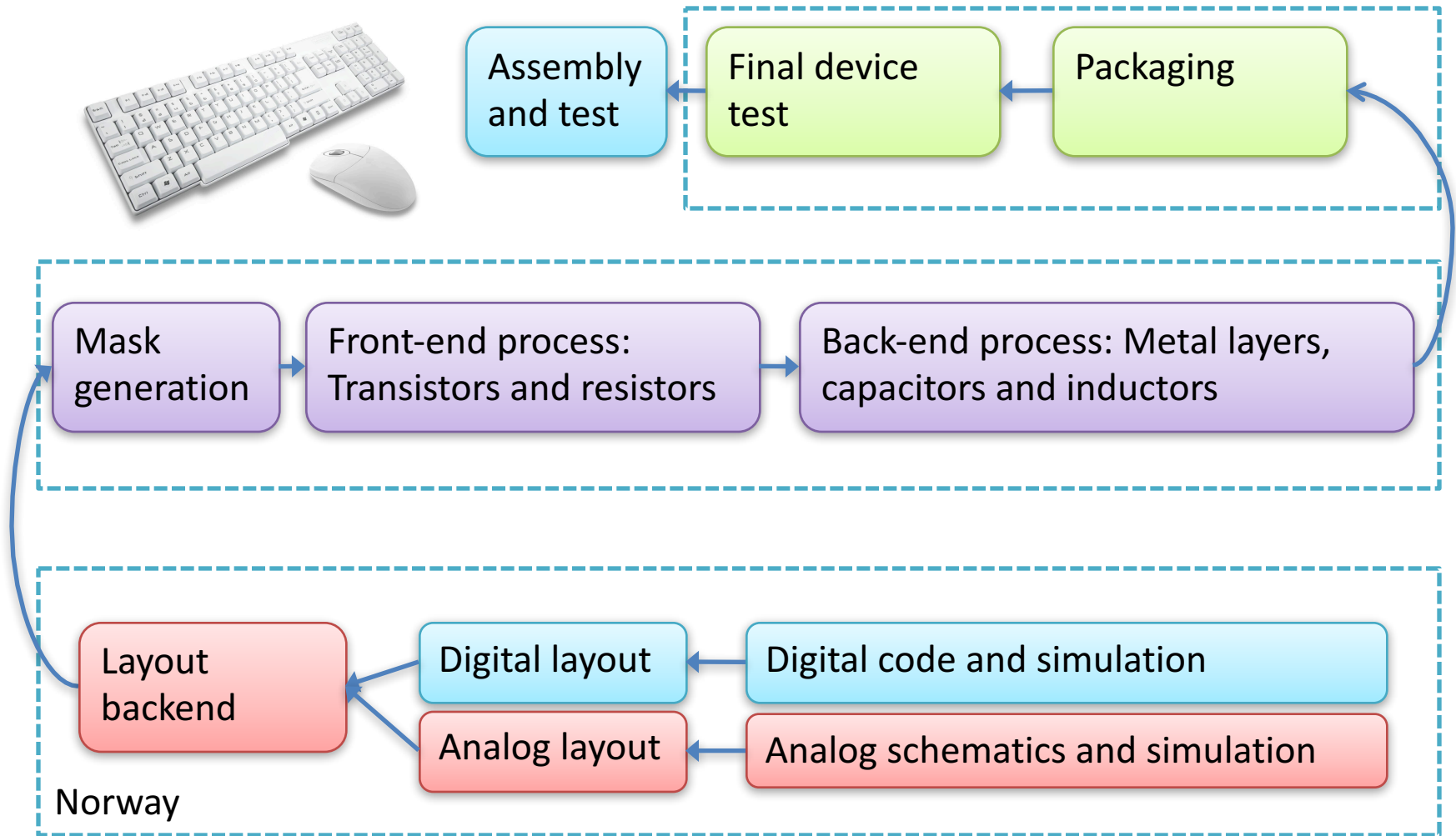
- Carsten Wulff
- Born Friday 13. August 1976
- Senior R & D engineer, wireless department at Nordic Semiconductor
- Married with three kids
- Graduated from NTNU 2002 (Programmable analog integrated circuit with TOC, 0.6um AMS)
- Ph.D from NTNU in 2008 (Efficient ADCs in nano-scale CMOS technology, 90nm ST)
- Fortunate to spend a year at University of Toronto (2006-2007) during my Ph.D
- <http://www.scribd.com/carstenwulff>
- <http://www.wulff.no/carsten>

Electronics research

Research takes time



The story



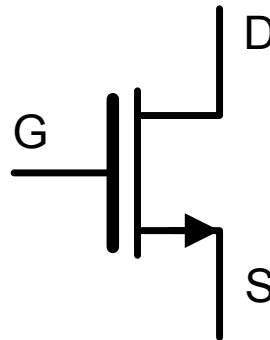
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- **Circuit elements**
- Processing
- Layout
- Schematics
- Advice for electronics students

Circuit elements

Transistor – The workhorse of ICs

- An extremely complicated device, but it's possible to make some assumptions



The accurate equation

$$I_D = f(W, L, \mu_n, C_{ox}, \dots, V_{GS}, V_{DS}, \dots) \text{ 284 parameters in BSIM 4.5}$$

The equation used for hand calculation in analog circuits

$$I_D \propto (V_{GS} - V_{th})^2$$

The equation sufficient for most digital designs

$$I_D \propto \begin{cases} \text{high, if } V_{GS} > V_{TH} \\ 0, \text{ if } V_{GS} < V_{TH} \end{cases}$$

Parameters for one transistor in BSIM 4.5

.MODEL N1 NMOS LEVEL=14 VERSION=4.5.0 BINUNIT=1 PARAMCHK=1 MOBMOD=0 CAPMOD=2 IGCMOD=1 IGBMOD=1 GEOMOD=1
 DIOMOD=1 RDSMOD=0 RBODYMOD=0 RGATEMOD=3 PERMOD=1 ACNQSMOD=0 TRNQSMOD=0 TEMPMOD=0 TNOM=27 **TOXE=1.8E-009**
 TOXP=10E-010 TOXM=1.8E-009 DTOX=8E-10 EPSROX=3.9 WINT=5E-009 LINT=1E-009 LL=0 WL=0 LLN=1 WLN=1 LW=0 WW=0 LWN=1
 WWN=1 LWL=0 WWL=0 XPART=0 TOXREF=1.4E-009 SAREF=5E-6 SBREF=5E-6 WLOD=2E-6 KU0=-4E-6 KVSAT=0.2 KVTH0=-2E-8 TKU0=0.0
 LLODKU0=1.1 WLODKU0=1.1 LLODVTH=1.0 WLODVTH=1.0 LKU0=1E-6 WKU0=1E-6 PKU0=0.0 LKVTH0=1.1E-6 WKVTH0=1.1E-6 PKVTH0=0.0
 STK2=0.0 LODK2=1.0 STETA0=0.0 LOETA0=1.0 LAMBDA=4E-10 VSAT=1.1E 005 VTL=2.0E5 XN=6.0 LC=5E-9 RNOIA=0.577 RNOIB=0.37
 LINTNOI=1E-009 WPEMOD=0 WEB=0.0 WEC=0.0 KVTH0WE=1.0 K2WE=1.0 KU0WE=1.0 SCREF=5.0E-6 TVOFF=0.0 TVFBSDOFF=0.0
VTH0=0.25 K1=0.35 K2=0.05 K3=0 K3B=0 W0=2.5E-006 DVT0=1.8 DVT1=0.52 DVT2=-0.032 DVT0W=0 DVT1W=0 DVT2W=0 DSUB=2
 MINV=0.05 VOFFL=0 DVTP0=1E-007 DVTP1=0.05 LPE0=5.75E-008 LPEB=2.3E-010 XJ=2E-008 NGATE=5E 020 NDEP=2.8E 018 NSD=1E 020
 PHIN=0 CDSC=0.0002 CDSCB=0 CDSCD=0 CIT=0 VOFF=-0.15 NFACTOR=1.2 ETA0=0.05 ETAB=0 UC=-3E-011 VFB=-0.55 **U0=0.032** UA=5.0E-
 011 UB=3.5E-018 A0=2 AGS=1E-020 A1=0 A2=1 B0=-1E-020 B1=0 KETA=0.04 DWG=0 DWB=0 PCLM=0.08 PDIBLC1=0.028 PDIBLC2=0.022
 PDIBLCB=-0.005 DROUT=0.45 PVAG=1E-020 DELTA=0.01 PSCBE1=8.14E 008 PSCBE2=5E-008 RSH=0 RDSW=0 RSW=0 RDW=0 FPROUT=0.2
 PDITS=0.2 PDITS0=0.23 PDITSL=2.3E 006 RSH=0 RDSW=50 RSW=150 RDW=150 RDSWMIN=0 RDWMIN=0 RSWMIN=0 PRWG=0
 PRWB=6.8E-011 WR=1 ALPHA0=0.074 ALPHA1=0.005 BETA0=30 AGIDL=0.0002 BGIDL=2.1E 009 CGIDL=0.0002 EGIDL=0.8 AIGBACC=0.012
 BIGBACC=0.0028 CIGBACC=0.002 NIGBACC=1 AIGBINV=0.014 BIGBINV=0.004 CIGBINV=0.004 EIGBINV=1.1 NIGBINV=3 AIGC=0.012
 BIGC=0.0028 CIGC=0.002 AIGSD=0.012 BIGSD=0.0028 CIGSD=0.002 NIGC=1 POXEDGE=1 FIGCD=1 NTOX=1 VFBSDOFF=0.0 XRCRG1=12
 XRCRG2=5 CGSO=6.238E-010 CGDO=6.238E-010 CGBO=2.56E-011 CGDL=2.495E-10 CGSL=2.495E-10 CKAPPAS=0.03 CKAPPAD=0.03
 ACDE=1 MOIN=15 NOFF=0.9 VOFFCV=0.02 KT1=-0.37 KT1L=0.0 KT2=-0.042 UTE=-1.5 UA1=1E-009 UB1=-3.5E-019 UC1=0 PRT=0
 AT=53000 FNOIMOD=1 TNOIMOD=0 JSS=0.0001 JSWS=1E-011 JSWGS=1E-010 NJS=1 IJTHSFWD=0.01 IJTHSREV=0.001 BVS=10 XJBVS=1
 JSD=0.0001 JSWD=1E-011 JSWGD=1E-010 NJD=1 IJTHDFWD=0.01 IJTHDREV=0.001 BVD=10 XJBVD=1 PBS=1 CJS=0.0005 MJS=0.5 PBSWS=1
 CJSWS=5E-010 MJSWS=0.33 PBSWGS=1 CJSWGS=3E-010 MJSWGS=0.33 PBD=1 CJD=0.0005 MJD=0.5 PBSWD=1 CJSWD=5E-010
 MJSWD=0.33 PBSWGD=1 CJSWGD=5E-010 MJSWGD=0.33 TPB=0.005 TCJ=0.001 TPBSW=0.005 TCJSW=0.001 TPBSWG=0.005
 TCJSWG=0.001 XTIS=3 XTID=3 DMCG=0E-006 DMCI=0E-006 DMCG=0E-006 DMCGT=0E-007 DWJ=0.0E-008 XGW=0E-007 XGL=0E-008
 RSHG=0.4 GBMIN=1E-010 RBPB=5 RBPB=15 RBPS=15 RBDB=15 RBPS=15 NGCON=1 JTSS=1E-4 JTSD=1E-4 JTSSWS=1E-10 JTSSWD=1E-10
 JTSSWGS=1E-7 JTSSWGD=1E-7 NJTS=20.0 NJTSSW=20 NJTSSWG=6 VTSS=10 VTSD=10 VTSSWS=10 VTSSWD=10 VTSSWGS=2 VTSSWGD=2
 XTSS=0.02 XTSD=0.02 XTSSWS=0.02 XTSSWD=0.02 XTSSWGS=0.02 XTSSWGD=0.02

$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} (V_{GS} - V_{th})^2$$

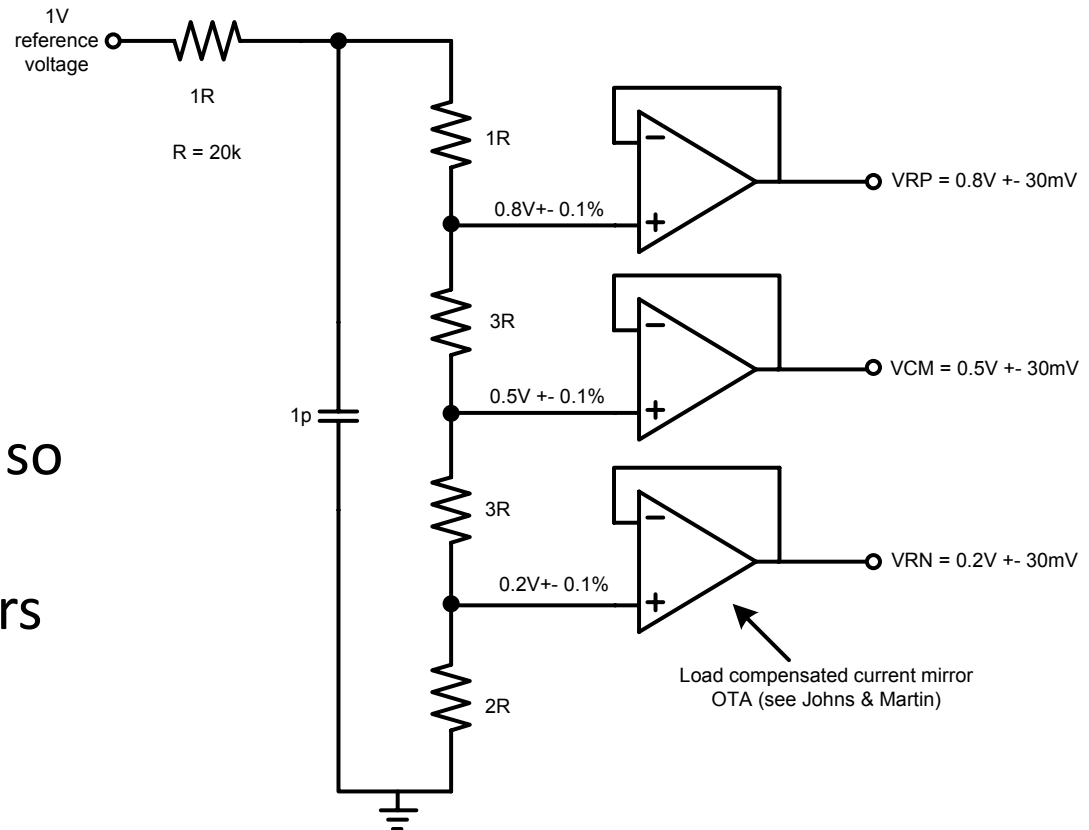
Integrated resistor – Master of ratios

- Most of the time a simple device



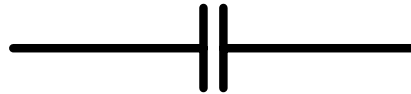
$$V = I R$$

- Very good matching between two resistors, so we can make very accurate voltage dividers



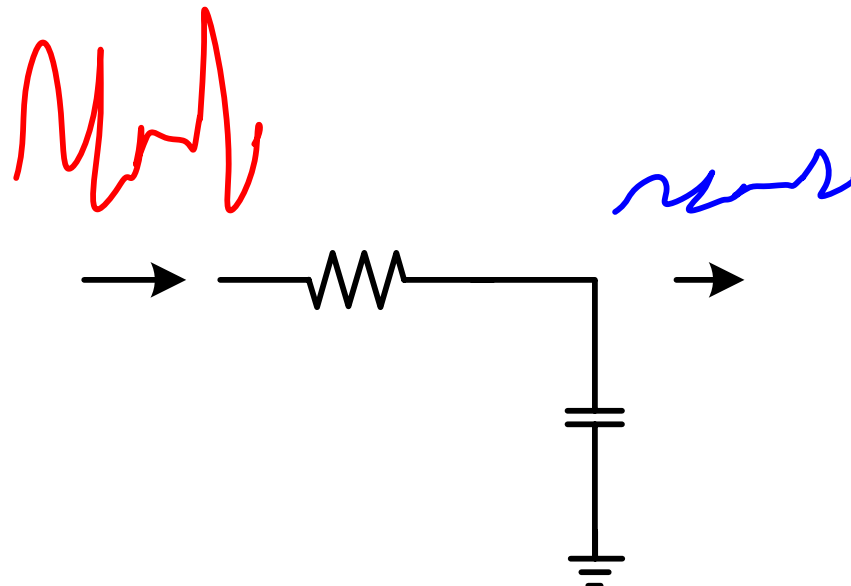
Integrated capacitor – Master of silence

- Not too hard either



$$i = C \, dv/dt$$

- Perfect for silencing a noisy power supply



Integrated inductor – Master of radio frequencies

- Principle is simple, not so easy to integrate on chip



$$V = L \, di/dt$$

- Used in sine wave generators, and radio frequency circuits

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Processing – Making an integrated circuit

| | | | | | | | | | | | | | |
|-----------------|---------------|--------------------|-----------------|------------------|-----------------|-----------------|------------------|-----------------|-------------------|-------------------|----------------|--------------------|-----------------|
| lanthanum 57 | cerium 58 | praseodymium 59 | neodymium 60 | promethium 61 | samarium 62 | europium 63 | gadolinium 64 | terbium 65 | dysprosium 66 | holmium 67 | erbium 68 | thulium 69 | ytterbium 70 |
| La | Ce | Pr | Nd | Pm | Sm | Eu | Gd | Tb | Dy | Ho | Er | Tm | Yb |
| 138.91 | 140.12 | 140.91 | 144.24 | [145] | 150.36 | 151.96 | 157.25 | 158.93 | 162.50 | 164.93 | 167.26 | 168.93 | 173.04 |
| actinium 89 | thorium 90 | protactinium 91 | uranium 92 | neptunium 93 | plutonium 94 | americium 95 | curium 96 | berkelium 97 | californium 98 | einsteinium 99 | fermium 100 | mendelevium 101 | nobelium 102 |
| Ac | Th | Pa | U | Np | Pu | Am | Cm | Bk | Cf | Es | Fm | Md | No |
| [227] | 232.04 | 231.04 | 238.03 | [237] | [244] | [243] | [247] | [247] | [251] | [252] | [257] | [258] | [259] |

- 15

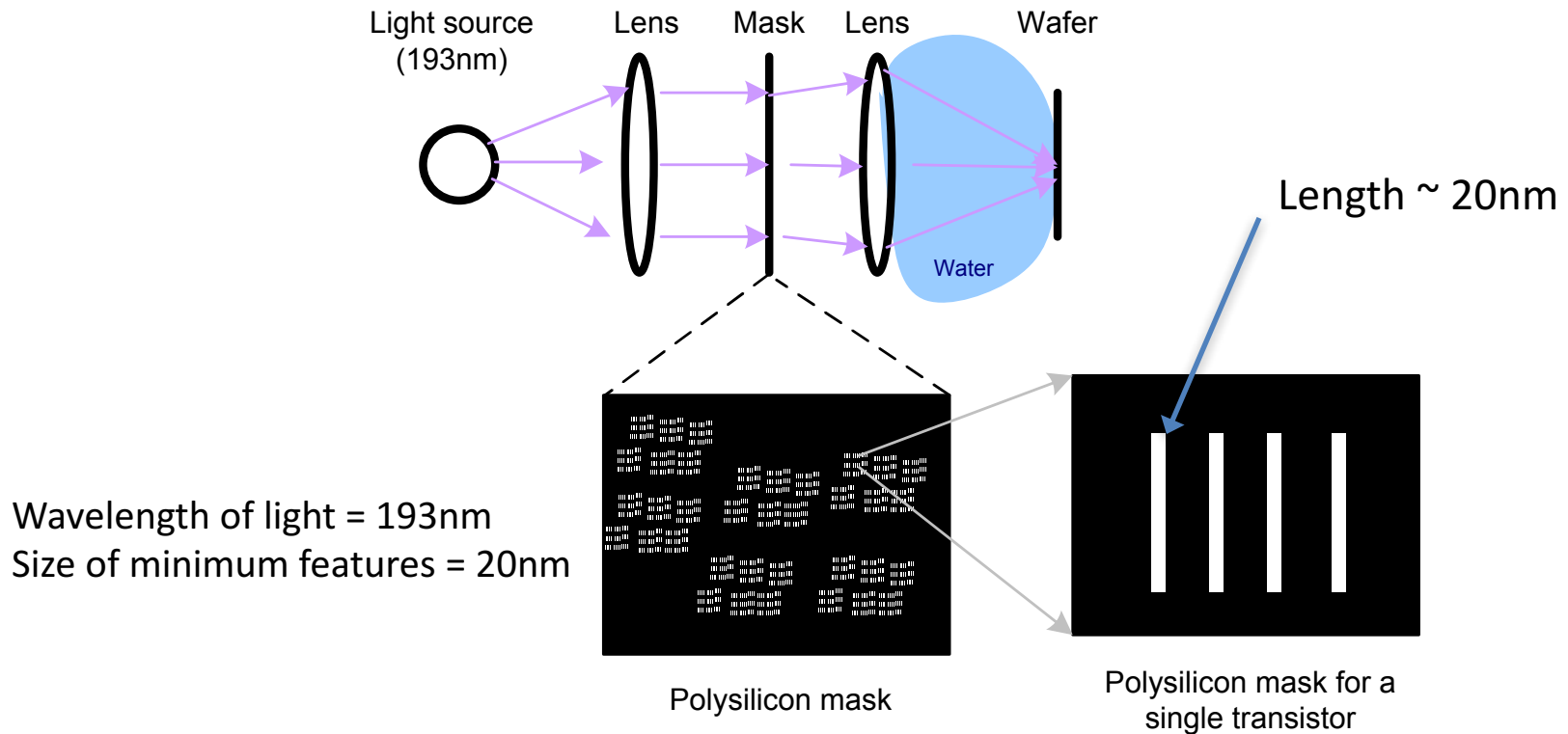
The wafer – the fundamental building block



<http://www.tomshardware.com/reviews/semiconductor-production-101,1590-3.html>

- Ingot = An ultra pure, single crystal of silicon
- Wafer = A very thin slice of an ingot, used as the first layer in processing

Photolithography

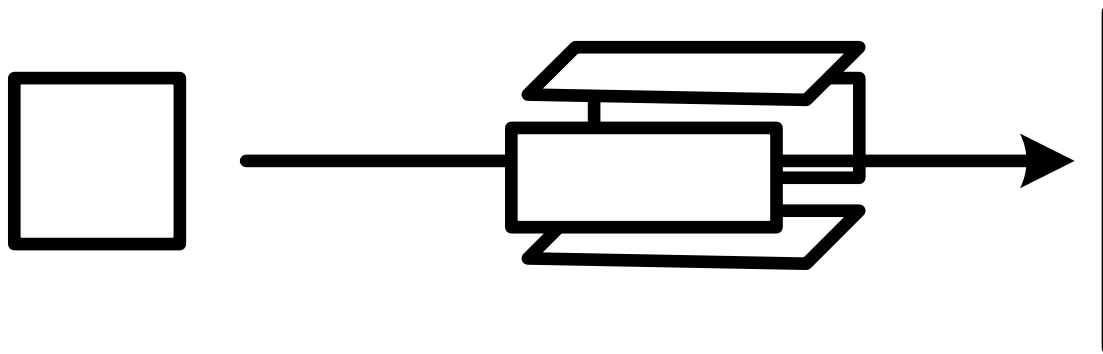


Mask generation

Electron gun

Lens

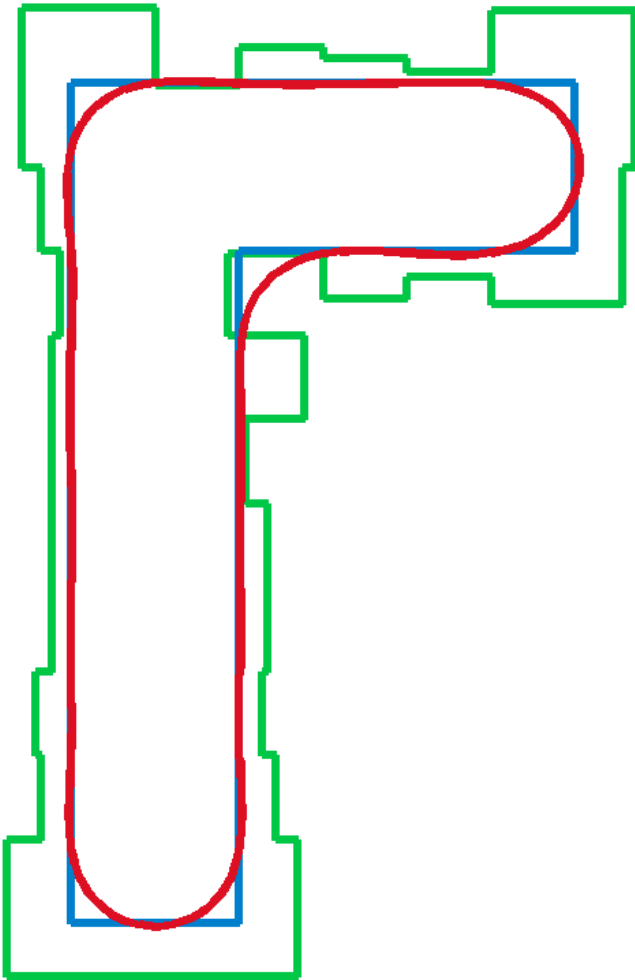
Mask



- Extremely expensive
- Must have higher accuracy than what we want to develop

| Minimum feature | Mask cost NOK |
|-----------------|---------------|
| 180nm | 600 000 |
| 65nm | 6 000 000 |
| 28nm | 30 000 000 |

Optical proximity correction (What you see is not what you get)



- The wavelength of the developing light is larger than minimum features ($193\text{nm} > 20\text{nm}$)
- Diffraction patterns affect the light intensity on the photo-resist
- Extensive calculations need to calculate how the mask should look to compensate for diffraction and processing inaccuracies

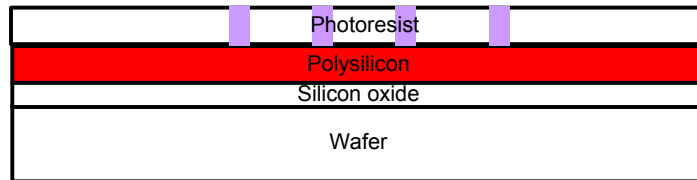
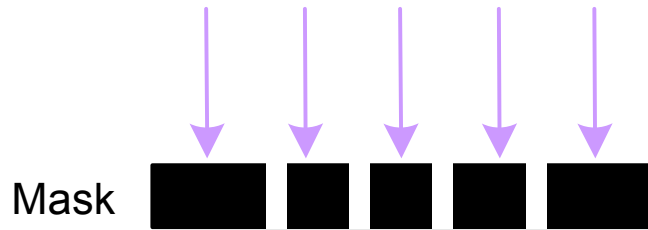
Blue = Pattern we draw in our CAD programs

Green = How the mask actually looks

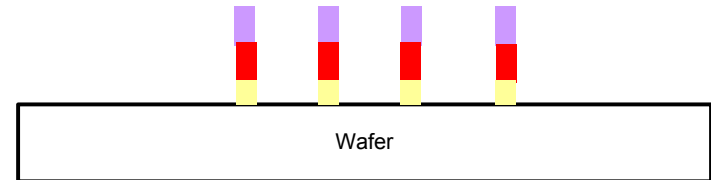
Red = Pattern on chip

http://upload.wikimedia.org/wikipedia/en/6/65/Optical_proximity_correction.png

Photo resist and development



1) Expose photoresist

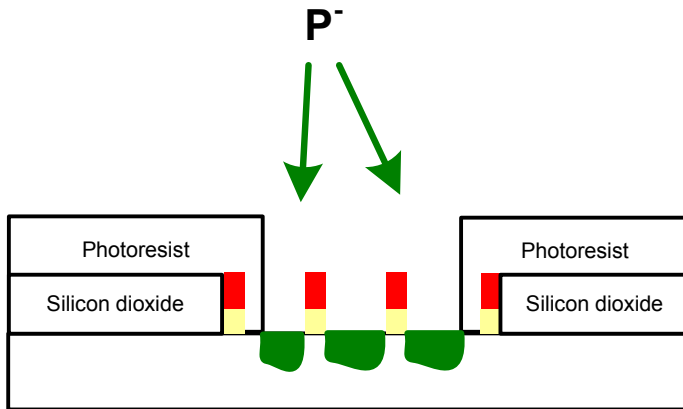


2) Remove photoresist and etch polysilicon

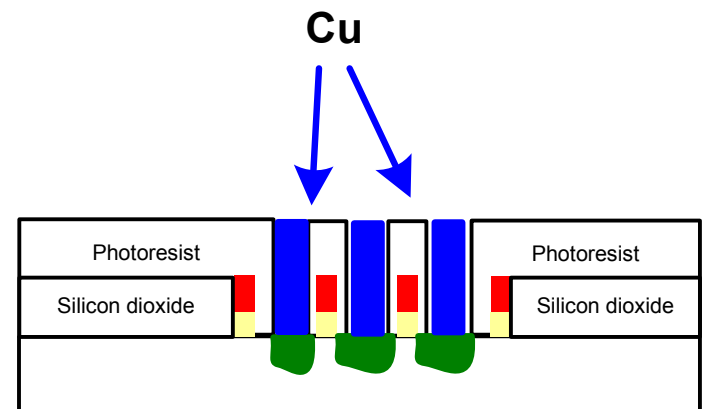
Toolbox

- Negative and positive photoresist
- Doping, etching, electroplating, vapor deposition

Doping and metal



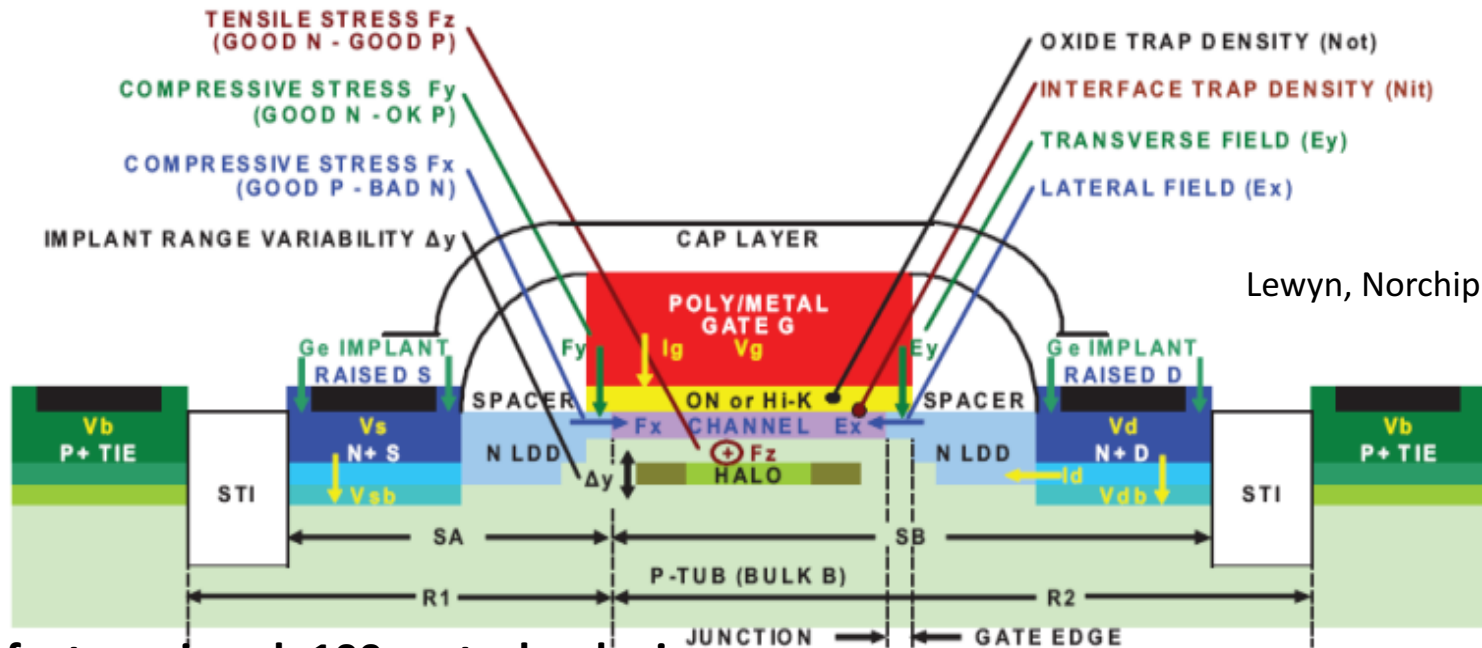
3) Add doping



4) Add metal

- Dopants change electrical properties of the silicon substrate
- Metal is added to wire up the circuit. In most processes the metal is copper.
- Up to nine metal layers in advanced processes

Nanoscale transistor

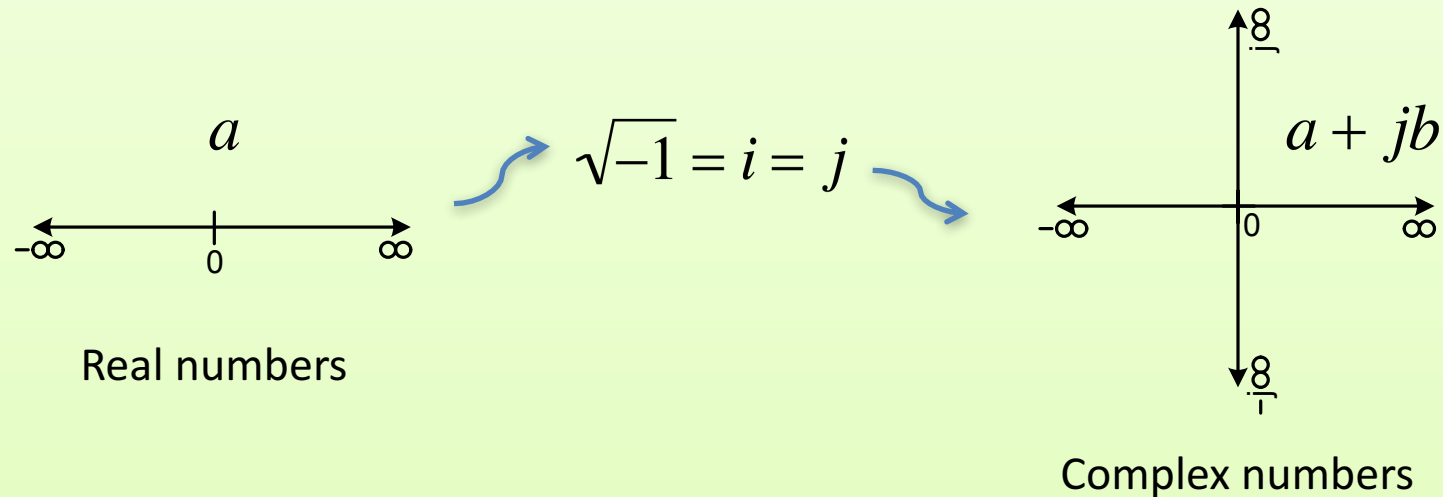


Lewyn, Norchip 2009

New features in sub 100nm technologies:

- Stress is actively used to increase mobility
- Very thin oxide, reduced power supply to keep vertical field in check
- Halo implant that increases drain-source conductance at longer channel lengths
- Hot carrier effects
- Stress from the STI (shallow trench isolation)
- Proximity to well edge
- Lithography issues since the minimum dimensions are less than the wavelength used to expose the photoresist ($\lambda=193\text{nm}$)

We digress: Complex math



$$Y(t) = I(t) + jQ(t)$$

Our radio uses a complex receiver (one path for I and one for Q), so you need to understand complex mathematics

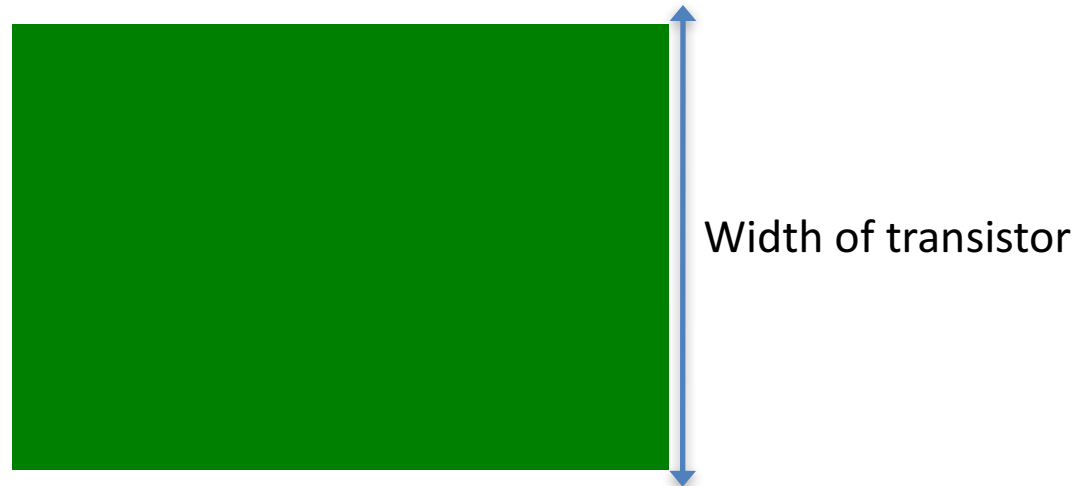
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Layout

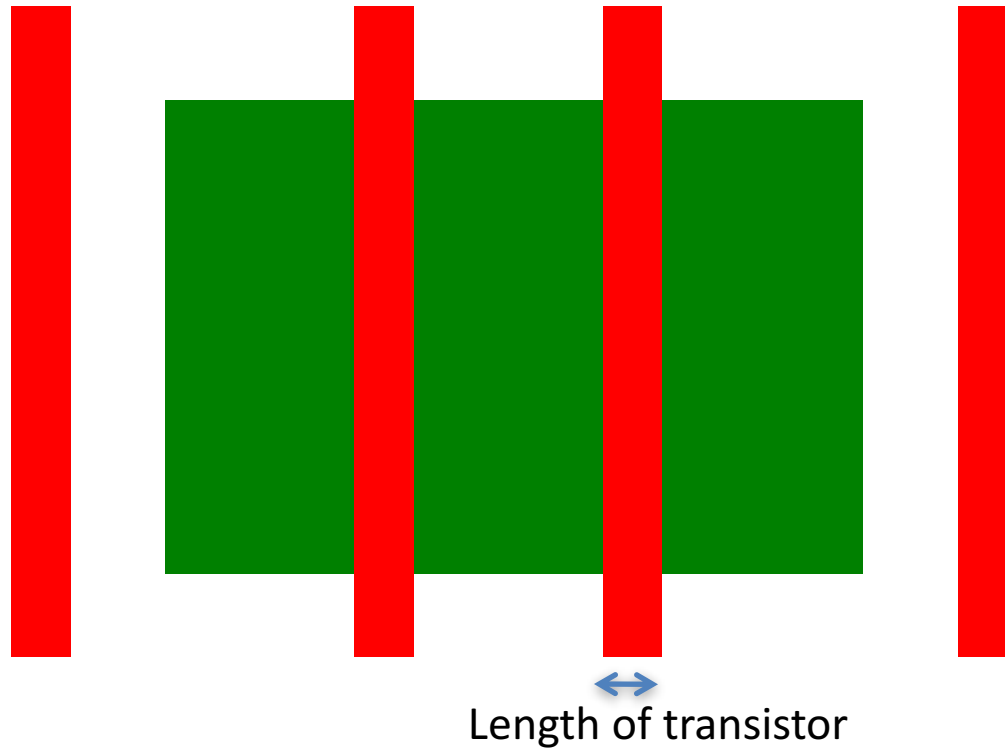
Let's make a transistor

Diffusion



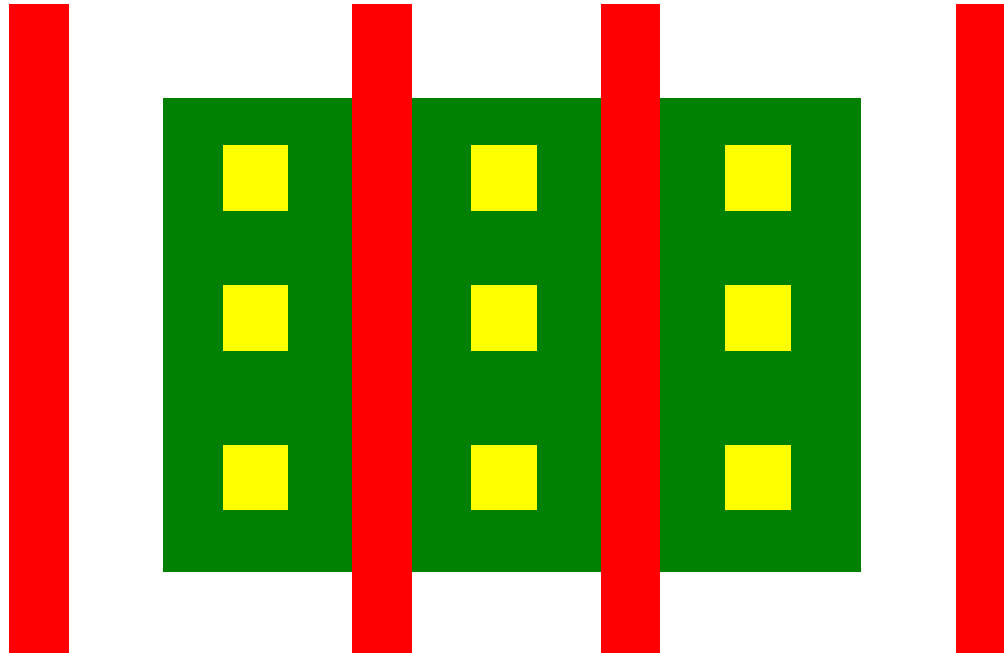
- Marks the boundry of the transistor
- Defines the width of the transistor

Polysilicon



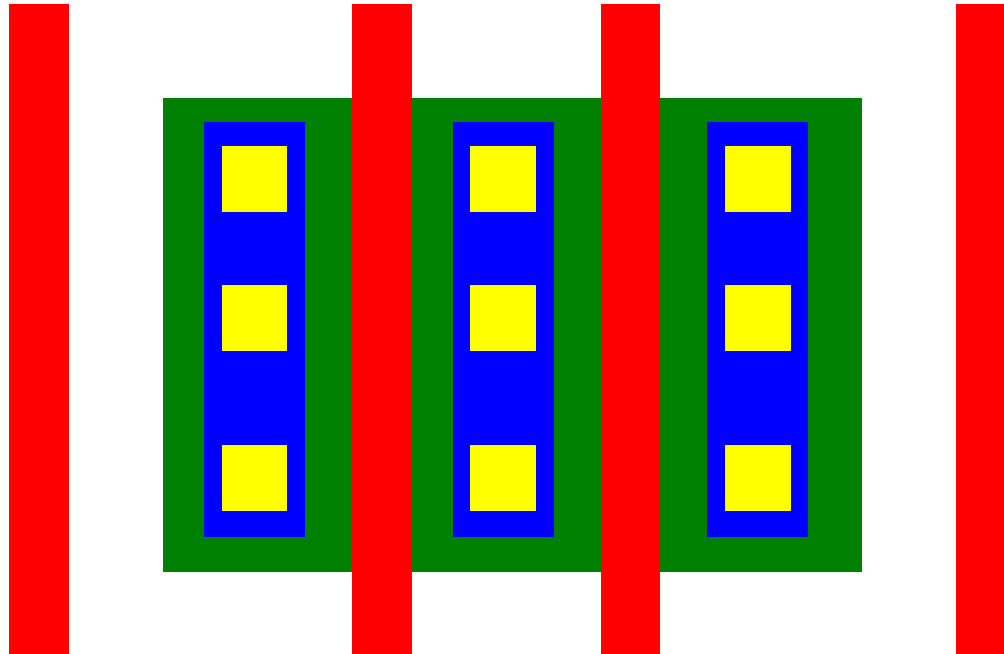
- The intersection of diffusion and polysilicon defines the transistor
- Polysilicon is the gate of the transistor, and sets the length

Contacts



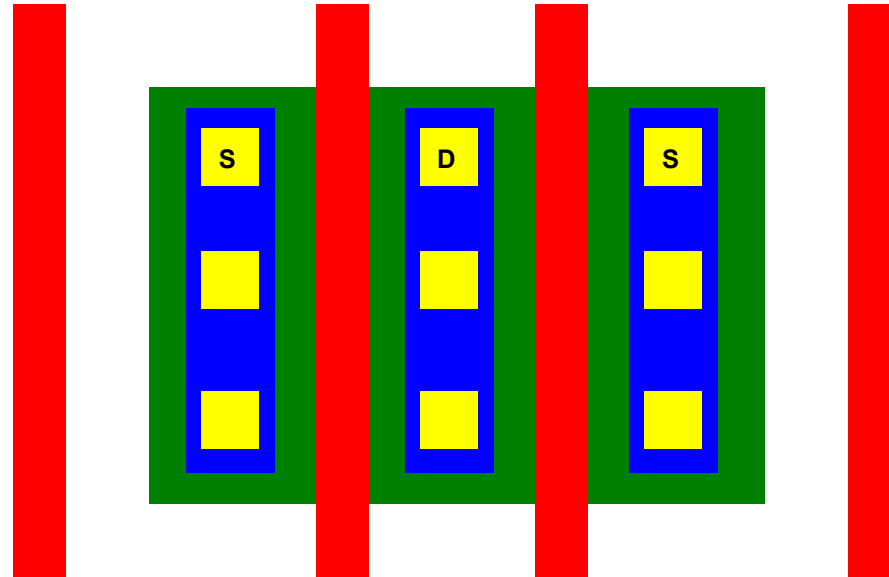
- Contacts are needed to connect between metal and diffusion

Metal



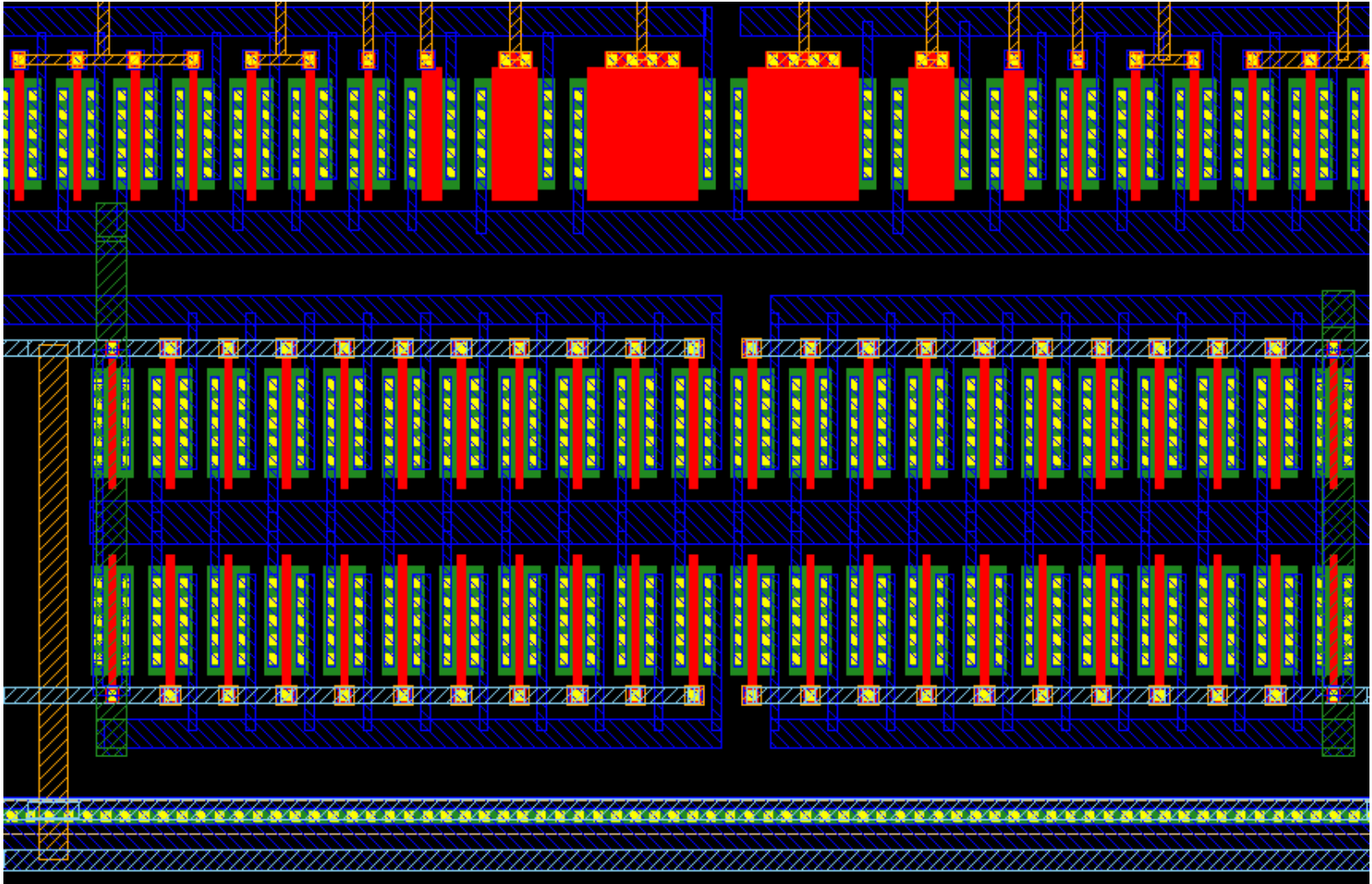
- Metal is used to connect one transistor to another

Transistor layout rules

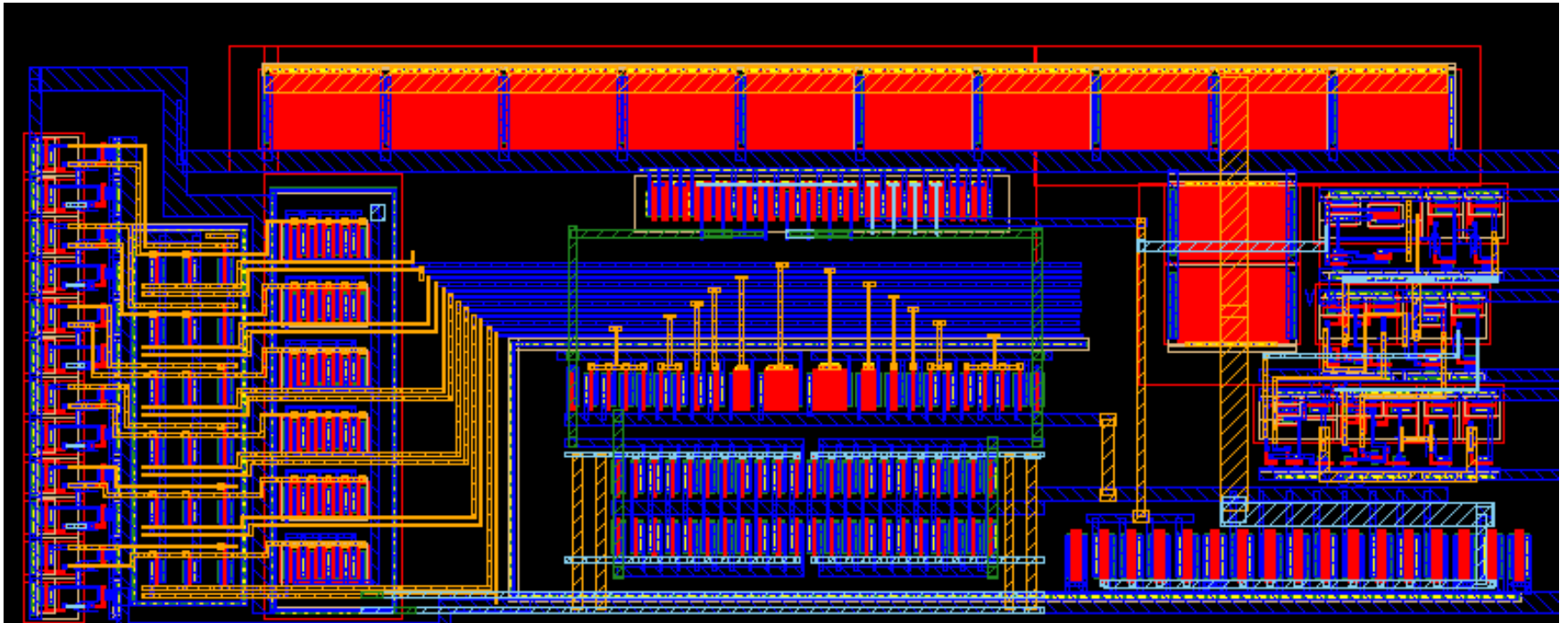


| Rule | Why |
|---|---|
| Always use two fingers | Transistor parameters change with current direction |
| Always run all gates in same direction | Stress in X and Y direction affect transistor differently |
| Always have dummy poly | Better poly control during processing |
| Always have larger than minimum length of diffusion | Less stress from shallow trench isolation |
| Always place transistors far from well edge | Reduce mismatch in threshold voltage |
| Be careful with metal routing across transistors | Metal changes the stress in the channel |

Layout of an opamp



Layout of opamp



Layout of an ADC

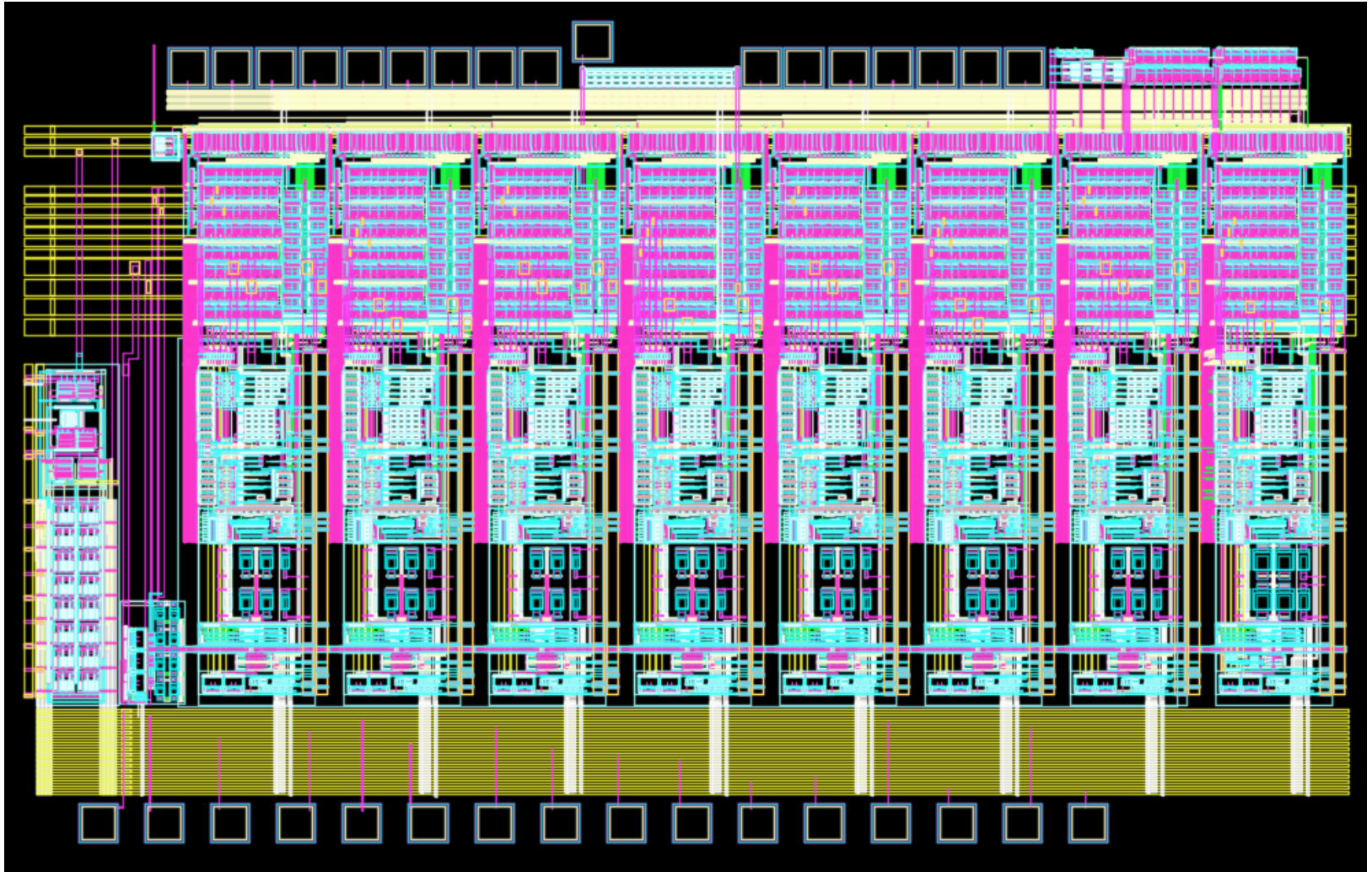
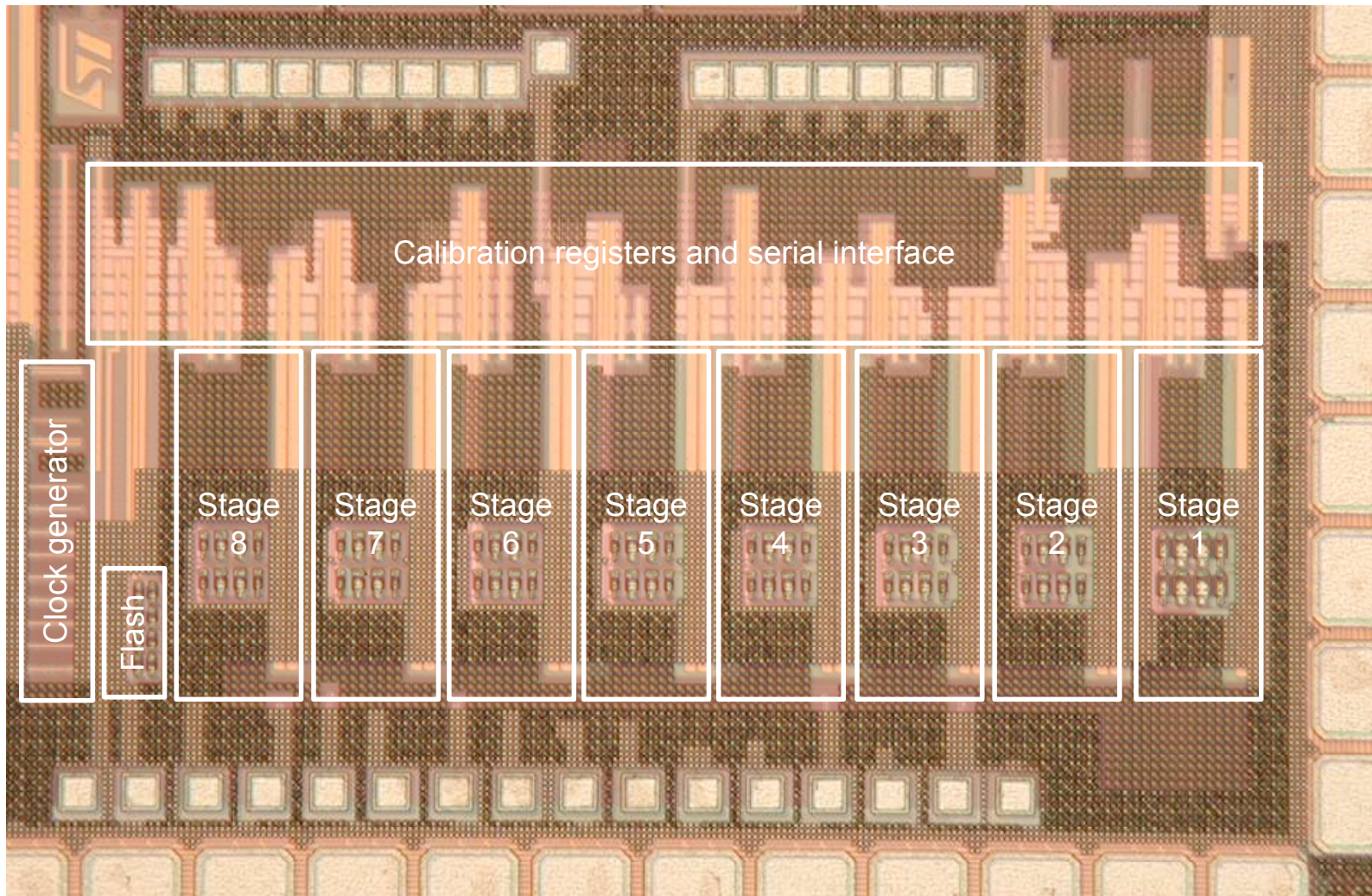


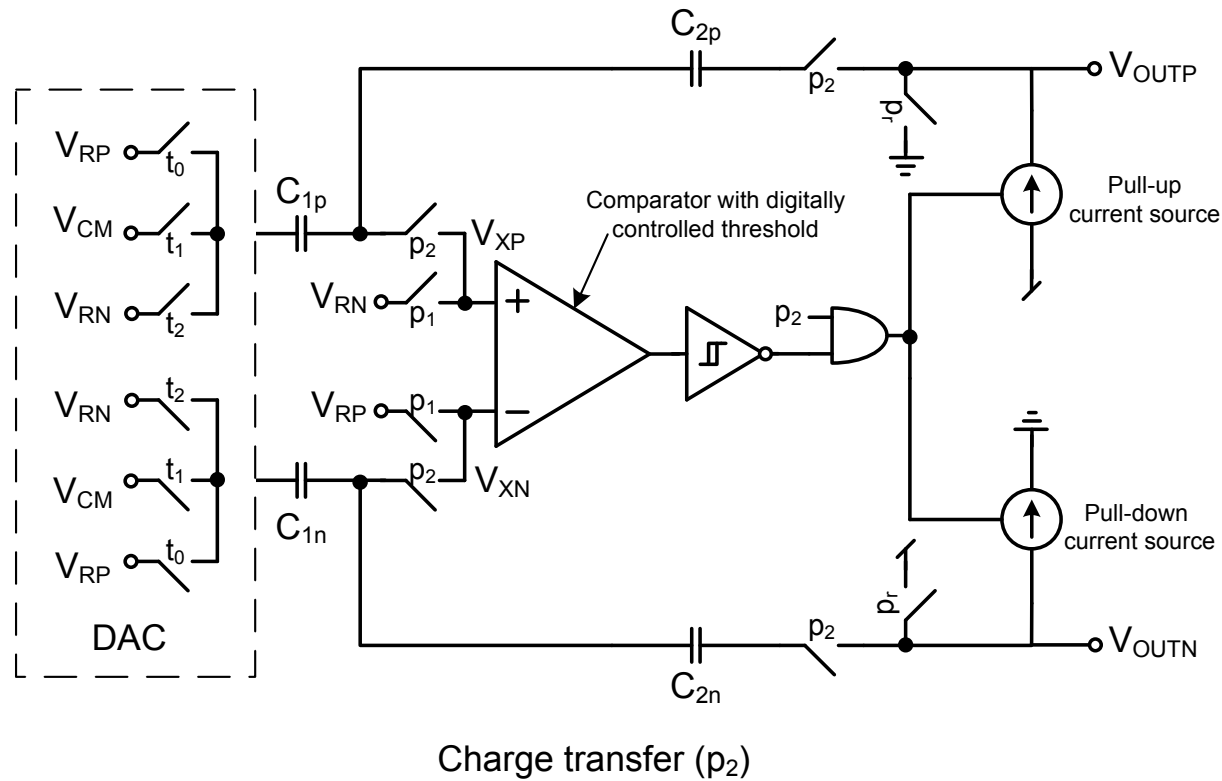
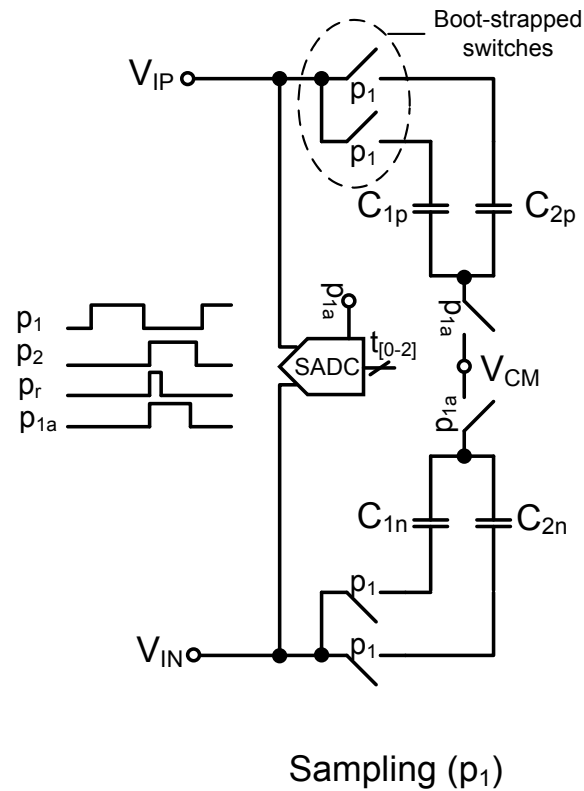
Image of an ADC



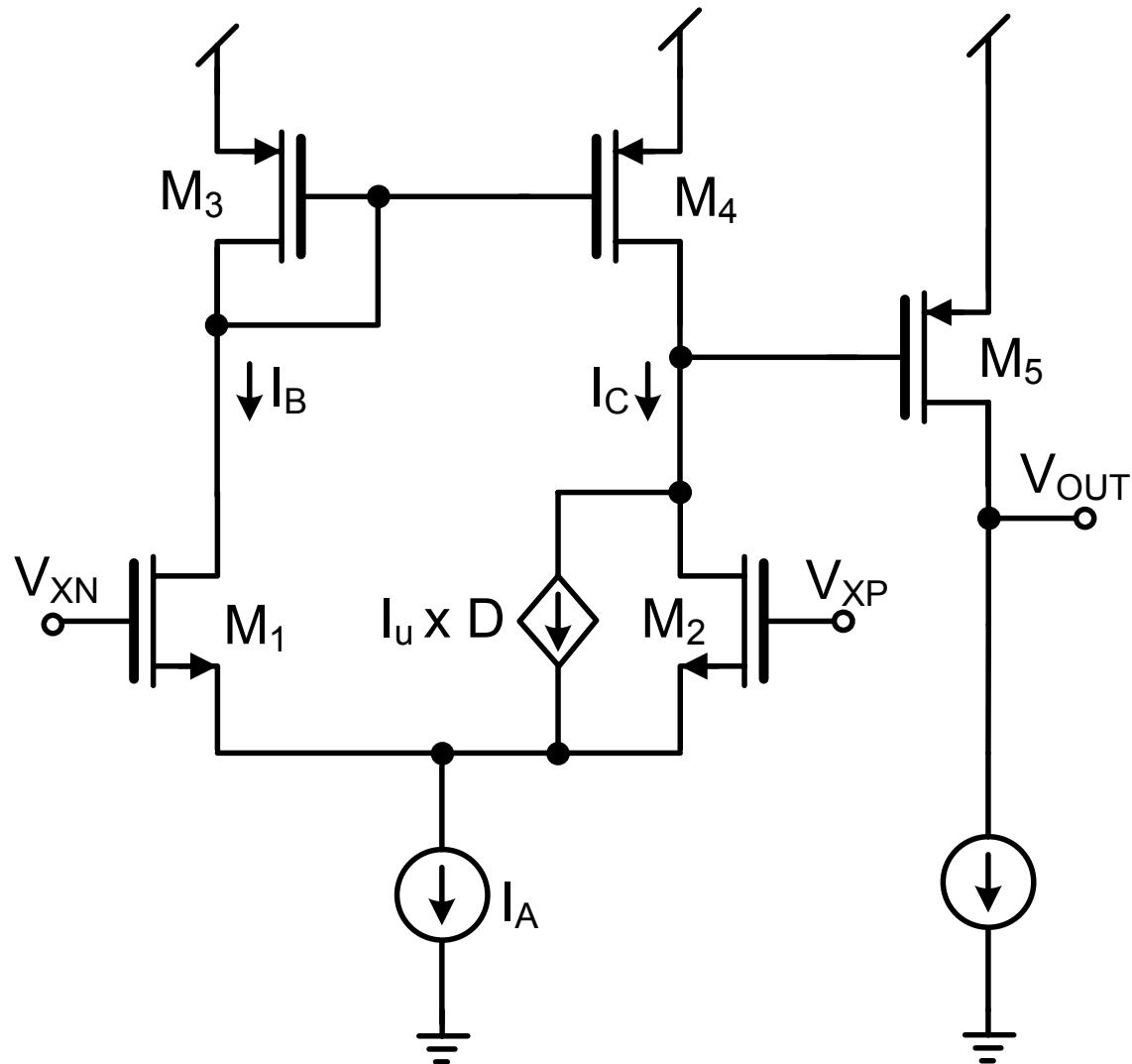
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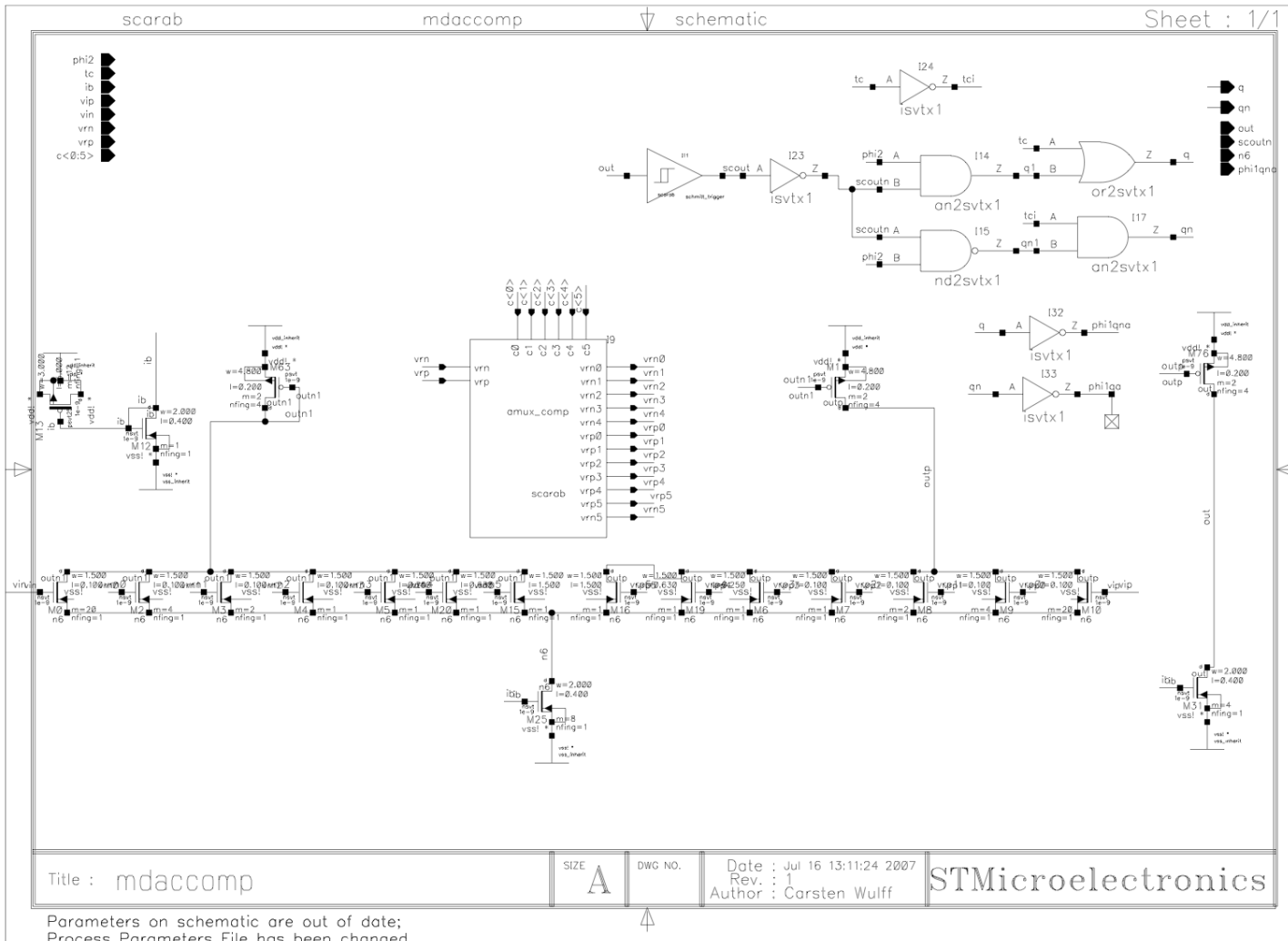
Schematics



Opamp schematic in Visio



Opamp schematic in Cadence



<http://www.wulff.no/carsten/lib/exe/fetch.php/carsten/pub/scarab.pdf>

Topics not covered

- Simulation, corner verification, monte-carlo simulation
- Digital design (Verilog)
- System level design (Matlab)
- Project management
- Lab testing
- Writing documentation

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Divide and conquer

- Break complex stuff down into smaller pieces
- Ignore the difficult stuff, and try to get an approximate understanding, then add inn the difficult stuff
- Don't be afraid if something is difficult
- Don't think your stupid and won't be able to understand
- Don't think that everybody else is smarter than you

When you don't understand

- Ask someone
- Don't be afraid to show that you don't know something, not knowing is OK (except on the exam, and in a job interview)
- Use wikipedia

Know your assumptions

- Assumption is your friend
- Assumption is your worst enemy
- Assumption is the mother of all mistakes

What you need to teach yourself

- Ability to work hard (constant speed)
- Programming
- Report writing
- Explaining things to other people
- Convincing people that your right through persuasive arguments

Last comments

- Assumptions are important (but handle with care)
- Learn your courses, they are important
- The world is your playground, if you're good enough you can make a lot of money, and make the world a better place

Questions?

Things you should know about

Software:

Schematic (Mentor graphics, Cadence, Synopsys, Tanner tools)

Layout (Mentor graphics, Cadence, Synopsys, Tanner tools)

Simulation (Eldo, Spectre, Hspice, SMASH)

Scripting (Bash, Perl, Python, TCL, LISP)

Editors (Emacs)

Math software (Matlab, Maple, Octave)

Information sources:

<http://ieeexplore.ieee.org>

<http://webcast.berkeley.edu/>

EE240 spring 2007 to spring 2010